

**In the Claims**

**Claim 1 (original): A nickel-vanadium sputtering component structure comprising at least 99.99 weight%, excluding gases, nickel and vanadium.**

**Claim 2 (original): The sputtering component structure of claim 1 being at least 99.995 weight%, excluding gases, nickel and vanadium.**

**Claim 3 (original): The sputtering component structure of claim 1 being at least 99.999 weight%, excluding gases, nickel and vanadium.**

**Claim 4 (original): The sputtering component structure of claim 1 as a sputtering target structure.**

**Claim 5 (original): The sputtering target structure of claim 4 as a sputtering target pre-fab.**

**Claim 6 (original): The sputtering target structure of claim 4 as a sputtering target.**

**Claim 7 (original): A nickel/vanadium sputtering component structure comprising at least 99.99 weight%, excluding gases, nickel and vanadium and having an average grain size throughout the structure of less than or equal to about 40 microns.**

**Claim 8 (original): The nickel/vanadium sputtering component structure of claim 7 as a sputtering component pre-fab.**

**Claim 9 (original): The nickel/vanadium sputtering component structure of claim 7 as a sputtering component.**

**Claim 10 (original): The nickel/vanadium sputtering component of claim 9 wherein the average grain size is less than or equal to about 30 microns.**

**Claim 11 (original): The nickel/vanadium sputtering component of claim 9 wherein the average grain size is less than or equal to about 20 microns.**

**Claim 12 (original): The nickel/vanadium sputtering component of claim 9 comprising from about 4 weight percent vanadium to about 10 weight percent vanadium.**

**Claim 13 (original): The nickel/vanadium sputtering component of claim 9 comprising about 7 weight percent vanadium.**

**Claim 14 (original): The nickel/vanadium sputtering component of claim 9 as a sputtering target.**

**Claim 15 (original): A layer sputter-deposited from the sputtering target of claim 14.**

**Claim 16 (original): The nickel/vanadium sputtering component of claim 9 comprising at least 99.995 weight%, excluding gases, nickel and vanadium.**

**Claim 17 (original): The nickel/vanadium sputtering component of claim 16 wherein the average grain size is less than or equal to about 30 microns.**

**Claim 18 (original): The nickel/vanadium sputtering component of claim 16 wherein the average grain size is less than or equal to about 20 microns.**

**Claim 19 (original): The nickel/vanadium sputtering component of claim 16 comprising from about 4 weight percent vanadium to about 10 weight percent vanadium.**

**Claim 20 (original): The nickel/vanadium sputtering component of claim 9 comprising at least 99.999 weight%, excluding gases, nickel and vanadium.**

**Claim 21 (original): The nickel/vanadium sputtering component of claim 20 wherein the average grain size is less than or equal to about 30 microns.**

**Claim 22 (original): The nickel/vanadium sputtering component of claim 20 wherein the average grain size is less than or equal to about 20 microns.**

**Claim 23 (original): The nickel/vanadium sputtering component of claim 20 comprising from about 4 weight percent vanadium to about 10 weight percent vanadium.**

Claims 24-39 (canceled).